

UNITED STATES PATENT AND TRADEMARK OFFICE
CERTIFICATE OF CORRECTIONPATENT NO. : 6,753,115 B2
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INVENTOR(S) : Zhang et al.

Page 1 of 1

It is certified that error appears in the above-identified patent and that said Letters Patent is hereby corrected as shown below:

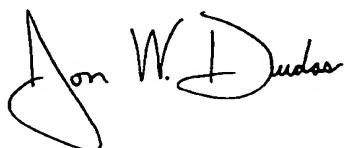
Column 14.

Line 65, after claim 32, please add the claim:

— “A mask used in fabricating an integrated circuit, wherein the mask is created through a method that facilitates minimum spacing or width control during an optical proximity correction operation for the mask, the method comprising:
considering a target edge of a first feature on the mask;
identifying a set of interacting edges in proximity to the target edge; and
performing the optical proximity correction operation, wherein performing the optical proximity correction operation involves applying a first edge bias to the target edge to compensate for optical effects in a resulting image of the target edge;
wherein applying the first edge bias to the target edge involves:
calculating an available bias based on minimum spacing requirements and/or minimum width requirements, and
allocating the available bias between the first edge bias for the target edge and a second edge bias for at least one edge in the set of interacting edges; and
wherein the available bias is allocated based on relative weights assigned to the target edge and the second edge.” —

Signed and Sealed this

Twenty-third Day of November, 2004



JON W. DUDAS
Director of the United States Patent and Trademark Office